

ASML PAS 5500/300C DUV Stepper

Instrument	Resist	Prebake	Exposure Time, PEB	Development
/300C	UV210-0.6	135°C, 60 sec.	20, 135°C, 90 sec.	726 MIF, 60 sec.
/300C	UV60	130°C, 60 sec.	24, 125°C, 60 sec.	726 MIF, 60 sec.
/300C	UV1400	130°C, 60 sec.	28, 110°C, 60 sec.	726 MIF, 60 sec.
/300C	GKR 4602PP	150°C, 90 sec.	35, 130°C, 90 sec.	726 MIF, 60 sec.
/300C	UVN2300 (negative)	110°C, 60 sec.	0.7, 110°C, 90 sec.	726 MIF, 30 sec.
/300C	DUV42P (ARC)	205°C, 60 sec.	n/a	n/a
/300C	DS-K101-4 (ARC)	175°C, 60 sec.	n/a	n/a

Note: all exposure times are approximate. Your process may be 0.5-2x these values or more.

The ASML /300C stepper uses 248nm illumination. These resists are specific to DUV; any other resists or materials should not be used without Staff approval. Output is approximately 200mW/cm² @248nm. Post exposure bake (PEB) is **required** for all of these photoresists.

Image reversal: is **not possible** with DUV resists.